Amendments to the Specification

Please replace the Abstract with the attached amended Abstract.

An exposure method is provided so that the dividend regions defined on a wafer ~~14~~ are successively exposed using pulses of laser light emitted from an excimer laser light source ~~1~~ in such a way that each region receives a different level of target exposure levels. And, transmittance of a course energy adjuster ~~3~~, having a number of neutral density filters, is adjusted so that a sub-divided region receiving the least number of exposure pulses can receive a pulse count that exceeds the minimum number of exposure pulses required for optimal exposure. During the process of scanning exposure, transmittance of the coarse energy adjuster is held constant so that, to compensate for variations in the pulse energy, the output power of the excimer laser light source ~~1~~ is adjusted according to real-time data output from an integrator sensor ~~25~~.